

External_Type	Material_Group	Substances	CAS_Number	Mass	Mass_Percentage_in_Leaf	Massmg
Die	Doped silicon	Silicon (Si)	7440-21-3	0.72	100.0	2.47
				Subtotal	0.72	100
						2.47
Post-plating	Pure metal	Tin (Sn)	7440-31-5	3.52	100.0	12
				Subtotal	3.52	100
						12
Lead Frame	Copper alloy	Phosphorous (P)	7723-14-0	0.02	0.03	0.05
	Copper alloy	Nickel (Ni) - cas no. 7440-02-0	7440-02-0	0.02	0.03	0.05
	Copper alloy	Iron (Fe)	7439-89-6	0.05	0.1	0.17
	Copper alloy	Copper (Cu)	7440-50-8	51.01	99.84	173.92
				Subtotal	51.1	100
						174.19
Mould Compound	Polymer	Phenol Formaldehyde resin (generic)	9003-35-4	2.63	6.0	8.96
	Polymer	Epichlorohydrin/Diethyleneglycol Epoxy resin (generic)	25928-94-3	3.07	7.0	10.45
	Filler	Silica fused	60676-86-0	37.66	86.0	128.4
	Carbon Black	Carbon black	1333-86-4	0.44	1.0	1.49
				Subtotal	43.8	100
						149.3
Wire	Pure metal	Aluminium (Al)	7429-90-5	0.04	100.0	0.15
	Pure metal	Aluminium (Al)	7429-90-5	0.15	100.0	0.5
				Subtotal	0.19	200
						0.65
Die Attach	Lead alloy	Tin (Sn)	7440-31-5	0.01	2.0	0.05
	Lead alloy	Silver (Ag)	7440-22-4	0.02	2.5	0.06
	Lead alloy	Lead (Pb)	7439-92-1	0.64	95.5	2.2
				Subtotal	0.67	100
						2.31
				Total	100	100
						340.92

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